

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L7	0	ep-1391533-\$ did.	US-PGPUB; USPAT	ADJ	ON	2007/05/03 11:27
L8	0	ep-1391533-\$ did.	US-PGPUB; USPAT; EPO	ADJ	ON	2007/05/03 11:03
L9	2	"1391533"	US-PGPUB; USPAT; EPO	ADJ	ON	2007/05/03 11:08
L10	0	ep-03254804-\$ did.	US-PGPUB; USPAT; EPO	ADJ	ON	2007/05/03 11:08
L11	8	(("6153313") or ("6255001") or ("6291084") or ("6287644") or ("3341307") or ("6207297") or ("6312584") or ("4109061")).PN.	US-PGPUB; USPAT	OR	OFF	2007/05/03 11:21
L12	8	(("6153313") or ("6255001") or ("6291084") or ("6287644") or ("3341307") or ("6207297") or ("5312584") or ("4109061")).PN.	US-PGPUB; USPAT	OR	OFF	2007/05/03 11:22
L13	1	("0560045").PN.	US-PGPUB; USPAT	OR	OFF	2007/05/03 11:24
L14	1	"0560045"	US-PGPUB; USPAT; EPO	ADJ	ON	2007/05/03 11:26
L15	0	ep-0560045-\$ did.	US-PGPUB; USPAT; EPO	ADJ	ON	2007/05/03 11:27
L16	1	ep-560045-\$ did.	US-PGPUB; USPAT; EPO	ADJ	ON	2007/05/03 11:27
L17	0	ep-391533-\$ did.	US-PGPUB; USPAT	ADJ	ON	2007/05/03 11:27
S1	1	ep-1391533-\$ did.	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2007/03/29 11:38
S2	11	target and "204".clas. and (IPD or (ion plasma deposition))	US-PGPUB; USPAT	ADJ	ON	2007/03/29 11:55
S3	159667	((atom percent) or (weight percent))	US-PGPUB; USPAT	ADJ	ON	2007/03/29 11:56
S4	11	"204".clas. and target and (IPD or (ion plasma deposition)) and ((atom percent) or (atom "%") or (weight percent) or (weight "%") or weight "%" or atom "%")	US-PGPUB; USPAT	ADJ	ON	2007/04/30 10:12

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S5	1	("6475642").PN.	US-PGPUB; USPAT	OR	OFF	2007/03/29 13:38
S6	57	(IPD or (ion plasma deposition)) and ((atom percent) or (atom "%") or (weight percent) or (weight "%") or weight "%" or atom "%") and (oxidation or oxidative) and (aluminum or Al) and (chromium or Cr)	US-PGPUB; USPAT	ADJ	ON	2007/04/30 10:36
S7	52	(IPD or (ion plasma deposition)) and ((atom percent) or (atom "%") or (weight percent) or (weight "%") or weight "%" or atom "%") and (oxidation or oxidative) and (aluminum or Al) and (chromium or Cr) and ((high temperature) or (high-temperature))	US-PGPUB; USPAT	ADJ	ON	2007/04/30 10:14
S8	2	(("6291084") or ("6153313")).PN.	US-PGPUB; USPAT	OR	OFF	2007/04/30 10:35
S9	0	(IPD or (ion plasma deposition)) and ((atom percent) or (atom "%") or (weight percent) or (weight "%") or weight "%" or atom "%") and (oxidation or oxidative) and (aluminum or Al) and (chromium or Cr) and "6291084".pn. and "6153313".pn.	US-PGPUB; USPAT	ADJ	ON	2007/04/30 10:37
S10	16	(IPD or (ion plasma deposition)) and ((atom percent) or (atom "%") or (weight percent) or (weight "%") or weight "%" or atom "%") and (oxidation or oxidative) and (aluminum or Al) and (chromium or Cr) and "6291084" and "6153313"	US-PGPUB; USPAT	ADJ	ON	2007/04/30 10:38
S11	0	(IPD or (ion plasma deposition)) and ((atom percent) or (atom "%") or (weight percent) or (weight "%") or weight "%" or atom "%") and (oxidation or oxidative) and (aluminum or Al) and (chromium or Cr) and ("6291084".pn. or "6153313".pn.)	US-PGPUB; USPAT	ADJ	ON	2007/04/30 10:40
S12	2	("6291084".pn. or "6153313".pn.)	US-PGPUB; USPAT	ADJ	ON	2007/04/30 10:40
S13	0	S12 and S6	US-PGPUB; USPAT	ADJ	ON	2007/04/30 10:40
S14	1	("5,516,380").PN.	US-PGPUB; USPAT	OR	OFF	2007/05/01 18:35

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S15	12	(IPD or (ion plasma deposition)) and ((atom percent) or (atom "%") or (weight percent) or (weight "%") or weight "%" or atom "%") and (oxidation or oxidative) and (aluminum or Al) and (chromium or Cr) and ((high temperature) or (high-temperature)) and (ingot or target) and (tantalum or Ta)	US-PGPUB; USPAT	ADJ	ON	2007/05/02 13:57
S16	2	(IPD or (ion plasma deposition)) and (oxidation or oxidative) and (aluminum or Al) and (chromium or Cr) and ((high temperature) or (high-temperature)) and (ingot or target) and (tantalum or Ta) and (silicon or Si) and volt	US-PGPUB; USPAT	ADJ	ON	2007/05/02 16:00
S17	6	(IPD or (ion plasma deposition)) and (oxidation or oxidative) and ((high temperature) or (high-temperature)) and (ingot or target) and ((bond coat) or (metal layer)) and volt	US-PGPUB; USPAT	ADJ	ON	2007/05/02 14:40
S18	9	(IPD or (ion plasma deposition)) and (ingot or target) and ((bond coat) or (metal layer)) and volt	US-PGPUB; USPAT	ADJ	ON	2007/05/02 14:39
S19	105	(PVD or (physical vapor deposition)) and (oxidation or oxidative) and (aluminum or Al) and (chromium or Cr) and ((high temperature) or (high-temperature)) and (ingot or target) and (tantalum or Ta) and (silicon or Si) and volt	US-PGPUB; USPAT	ADJ	ON	2007/05/02 14:41
S20	0	(PVD or (physical vapor deposition)) and (oxidation or oxidative) and ((high temperature) or (high-temperature)) with ((aluminum or Al) and (chromium or Cr) and (ingot or target) and (tantalum or Ta) and (silicon or Si) and volt)	US-PGPUB; USPAT	ADJ	ON	2007/05/02 14:42
S21	0	(PVD or (physical vapor deposition)) and (oxidation or oxidative) and ((high temperature) or (high-temperature)) and (((aluminum or Al) and (chromium or Cr) and (ingot or target) and (tantalum or Ta) and (silicon or Si)) with volt)	US-PGPUB; USPAT	ADJ	ON	2007/05/02 14:44

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S22	105	(PVD or (physical vapor deposition)) and (oxidation or oxidative) and ((high temperature) or (high-temperature)) and ((aluminum or Al) and (chromium or Cr) and (ingot or target) and (tantalum or Ta) and (silicon or Si)) and volt	US-PGPUB; USPAT	ADJ	ON	2007/05/02 14:49
S23	5	stollenwerk.in. and "204".clas.	US-PGPUB; USPAT	ADJ	ON	2007/05/02 14:57
S24	63	chiang.in. and "204".clas.	US-PGPUB; USPAT	ADJ	ON	2007/05/02 16:43
S25	0	(IPD or (ion plasma deposition)) and (target and ingot) and volt	US-PGPUB; USPAT	ADJ	ON	2007/05/02 16:03
S26	0	(IPD or (ion plasma deposition)) and (target and ingot) and voltage	US-PGPUB; USPAT	ADJ	ON	2007/05/02 16:03
S27	0	(IPD or (ion plasma deposition)) and (target and ingot) and amp	US-PGPUB; USPAT	ADJ	ON	2007/05/02 16:03
S28	32	(IPD or (ion plasma deposition)) and (target or ingot) and volt	US-PGPUB; USPAT	ADJ	ON	2007/05/02 16:12
S29	61	(IPD or (ion plasma deposition)) and (target or ingot) and (volt or amp)	US-PGPUB; USPAT	ADJ	ON	2007/05/02 16:17
S30	2	(IPD or (ion plasma deposition)) and (negative potential bias)	US-PGPUB; USPAT	ADJ	ON	2007/05/02 16:18
S31	42	(IPD or (ion plasma deposition)) and (bias with substrate)	US-PGPUB; USPAT	ADJ	ON	2007/05/02 16:29
S32	2666	((IPD or (ion plasma deposition)) or (pvd or (physical vapor deposition))) and (bias with substrate)	US-PGPUB; USPAT	ADJ	ON	2007/05/02 16:30
S33	2451	((IPD or (ion plasma deposition)) or (pvd or (physical vapor deposition))) and (bias with substrate) and (aluminum or al)	US-PGPUB; USPAT	ADJ	ON	2007/05/02 16:30
S34	960	((IPD or (ion plasma deposition)) or (pvd or (physical vapor deposition))) and (bias with substrate) and (aluminum or al) and (nickel or ni)	US-PGPUB; USPAT	ADJ	ON	2007/05/02 16:31
S35	211	((IPD or (ion plasma deposition)) or (pvd or (physical vapor deposition))) and (bias with substrate) and (aluminum or al) and (nickel or ni) and (chromium or Cr) and volt	US-PGPUB; USPAT	ADJ	ON	2007/05/02 16:32

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S36	105	((IPD or (ion plasma deposition)) or (pvd or (physical vapor deposition))) and (bias with substrate) and (aluminum or al) and (nickel or ni) and (chromium or Cr) and volt and (high-temperature or (high temperature))	US-PGPUB; USPAT	ADJ	ON	2007/05/02 16:33
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